



Brazing Flux BrazeTec H 285 PASTE

TD EN H 285 PASTE REV.2

Composition and technical data:

Composition (% in weight)	Potassium Tetrafluoroborate 20-30 20-30	Distillate Potassium Hydroxide 0,5-2
Colour	Brown	
Working temperature (°C)	520-910	
Density (g/cm ³)	1,1	
Chemical characteristics	Partially water soluble	
PH	-	
Solubility	Partially water soluble	
State of product	Paste	
Residues	Residues are corrosive and have to be removed with water and mechanical rubbing	
Standard DIN EN 1045	FH12	
Shelf life	Min. 6 months, but only in the original sealed container at storage temperatures between +5 to +30 °C.	

Applications

Tool and electrical industry, automotive

Operating conditions

Flux for brazing process. Excellent for removing surface oxides. Used for brazing metallic materials which are difficult to wet, such as cemented carbides, copper, copper alloys, as well as nickel, nickel alloys and stainless steel. Suitable for dispenser application in automated brazing process.

Recommended alloys

BrazeTec 7200, 6488, 6009, 5662, 5081, 4900, 4911, 4900A, 4085, 2700, 21/80, 21/68, 49Cu,49Cu13,49/NiN,64/Cu, 49Cuplus

Heat source

Flame, induction heating

Notes

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